



09/408,279

PATENT

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

John Rosato et al.

Application No.: 09/408,279

Filed: September 29, 1999

For: PROCESS AND SYSTEM FOR
RINSING OF SEMICONDUCTOR
SUBSTRATES

Group Art Unit: 1746

Examiner: M. Kornakov

RESPONSE TO OFFICIAL ACTION
MAILED JUNE 13, 2002

121 Spear Street, Suite 290
San Francisco, CA 94105
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Commissioner for Patents
Washington, D.C. 20231

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope, addressed to: Commissioner for Patents, Washington, DC 20231 on December 13, 2002.

STALLMAN & POLLOCK LLP

Dated: 12/13/2002

By:

Georgia K. Stith
Georgia K. Stith

Sir:

Applicants make the following amendments and remarks in response to the official action mailed June 13, 2002.

IN THE CLAIMS ✓

Please cancel Claim 81.

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TC 1700

Please amend claims 80, 83, 88-90 and 98:

80. (AMENDED) A method for rinsing metallized semiconductor substrates following treatment of the substrates with an etch residue removal chemistry, the method comprising the steps of:

providing at least one metallized semiconductor substrate, the substrate having etch residue removal chemistry thereon; and

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Atty Docket No.: SCP-6620